

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Docket No: Q84137

Shinichi ISHIBASHI, et al.

Allowed: February 7, 2008

Appln. No.: 10/510,916

Group Art Unit: 1795

Confirmation No.: 7320

Examiner: Stephen D. Rosasco

Filed: October 12, 2004

For: REFLECTIVE MASK BLANK, REFLECTIVE MASK AND METHODS OF
PRODUCING THE MASK BLANK AND THE MASK

INFORMATION DISCLOSURE STATEMENT
UNDER 37 C.F.R. §§ 1.97 and 1.98

MAIL STOP ISSUE FEE

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Sir:

In accordance with the duty of disclosure under 37 C.F.R. § 1.56, Applicant hereby notifies the U.S. Patent and Trademark Office of the documents which are listed on the attached PTO/SB/08 A & B (modified) form and/or listed herein and which the Examiner may deem material to patentability of the claims of the above-identified application.

One copy of each of the listed documents is submitted herewith, along with a copy of the corresponding Communication from a Foreign Patent Office, except for the following: U.S. patents and/or U.S. patent publications; and co-pending non-provisional U.S. applications filed after June 30, 2003.

The present Information Disclosure Statement is being filed after either a Final Office Action, Notice of Allowance, or an action that otherwise closes prosecution in the application

(whichever is earlier), but before payment of the Issue Fee, and therefore the fee of \$180.00 under 37 C.F.R. § 1.17(p) is submitted herewith through the EFS Deposit Account, with a Statement Under 37 C.F.R. § 1.97(e) and a copy of a Communication from a foreign patent office dated January 16, 2008 in a counterpart application citing such documents.

JP 2001-237174 was previously cited in the Information Disclosure Statement filed June 9, 2005. M. Takahashi., et al, Smooth Low-stress sputtered tantalum and tantalum alloy films for the absorber material of reflective-type EUVL” was previously cited in the Information Disclosure Statement filed December 5, 2007.

The submission of the listed documents is not intended as an admission that any such document constitutes prior art against the claims of the present application. Applicant does not waive any right to take any action that would be appropriate to antedate or otherwise remove any listed document as a competent reference against the claims of the present application.

The USPTO is directed and authorized to charge all required fees, except for the Issue Fee and the Publication Fee, to Deposit Account No. 19-4880. Please also credit any overpayments to said Deposit Account. A duplicate copy of this paper is attached.

Respectfully submitted,

/Alan J. Kasper/

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WASHINGTON OFFICE

23373

CUSTOMER NUMBER

Alan J. Kasper
Registration No. 25,426

Date: April 18, 2008

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STATEMENT UNDER 37 C.F.R. § 1.97(e)

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Alexandria, VA 22313-1450

Sir:

The undersigned hereby states, upon information and belief:

That each item of information contained in the Information Disclosure Statement filed
concurrently herewith was first cited in any communication from a foreign patent office in a
counterpart foreign application not more than three months prior to the filing of said Information
Disclosure Statement.

Respectfully submitted,

/Alan J. Kasper/

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